

<b>Session Title:</b>	<b>[WA3] Nanoscale Thin Film Deposition VIII</b>
<b>Session Date:</b>	<b>November 16 (Wed.), 2022</b>
<b>Session Time:</b>	<b>15:10-16:10</b>
<b>Session Room:</b>	<b>Room A (Capri Room, 2F)</b>
<b>Session Chair:</b>	<b>Prof. Hyeongtag Jeon (Hanyang Univ., Korea)</b>

**[WA3-1]** 15:10-15:30

**Development of Low-k Smart PECVD Equipment and Process for System LSI Devices**

SM Lee, JY Yang, SW Lee, SH Yeo (TES Co., Ltd., Korea), TJ Choi (Sejong Univ., Korea), JK Lee (Pusan Nat'l Univ., Korea), JO Kim (KRISS, Korea), and HJ Jang (TES Co., Ltd., Korea)

**[WA3-2]** 15:30-15:50

**Characteristic Evaluation of  $\text{Si}_x\text{Sn}_y\text{O}_z$  Thin Film for Encapsulation of OLED**

Sang Yong Jeon, Ha Yeong Ahn, Young Jae Im, Sang Chan Lee, Yong Hee Kwone, Tae Seok Byun, and Sang Ick Lee (DNF Co., Ltd., Korea)

**[WA3-3]** 15:50-16:10

**Advanced Remote Plasma ALD for Self-Aligned Patterning Technology**

Suhyeon Park, Junyoung An, Heejun Yoon (Hanyang Univ., Korea), Honggyu Kim (Univ. of Florida, USA), and Hyeongtag Jeon (Hanyang Univ., Korea)